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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Juing-Yi Cheng et al.

Serial No.: 10/697.833

Filed: October 30, 2003

For: A Method of Improving Short
Channel Effect and Gate Oxide Reliability by
Nitrogen Plasma Treatment Before Space
Deposition

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Attorney Docket No.:
24061.470/TS02-150

Group Art Unit: 2823

Examiner: Dang, Trung Q

Commissioner for Patents
Mail Stop Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

No fees, including extension of time fees, are believed necessary for consideration of the present paper. However, if any fees, including extension of time fees, are necessary, the extension of time is hereby requested, and the Commissioner is hereby authorized to charge any fees, including those for the extension of time, to Haynes and Boone, LLP's Deposit Account No. 08-1394.

In response to the office action of September 22, 2005, please amend the above-identified application as follows:

Listing of claims begins on **page 2** of this paper.

Remarks begin on **page 10** of this paper.